

Industrial Session Program

September 30 (Mon) 19:00-21:00

Room: Tenzui

Chairperson: T. Fujimoto (Nippon Steel & Sumitomo Metal, Japan)

19:00 - 19:05 Cree Inc.
19:05 - 19:10 Nippon Steel & Sumikin Materials Co., Ltd.
19:10 - 19:15 Dow Corning Corporation
19:15 - 19:20 II-VI Japan Inc.
19:20 - 19:25 Norstel AB
19:25 - 19:30 Ceramicforum.Co.,Ltd.
19:30 - 19:35 TanKeBlue Semiconductor Co., Ltd.
/ New Metals and Chemicals Corp., Ltd.
19:35 - 19:40 Aymont Technology, Inc.
19:40 - 19:45 SKC Co., Ltd
19:45 - 19:50 SICC
19:50 - 19:55 SHOWA DENKO K.K.
19:55 - 20:00 Fraunhofer Institute IISB
20:00 - 20:05 Tianyu Semiconductor Technology Co.,Ltd.
20:05 - 20:10 EpiWorld International Co., Ltd.
20:10 - 20:15 TOKYO ELECTRON
20:15 - 20:20 AIXTRON
20:20 - 20:25 LPE S.P.A.
20:25 - 20:30 TAKACHIHO CHEMICAL INDUSTRIAL CO., LTD.
20:30 - 20:35 Momentive Performance Materials Japan LLC
20:35 - 20:40 STR Japan K.K.
20:40 - 20:45 Takano Co.,Ltd
20:45 - 20:50 Renishaw KK
20:50 - 20:55 Nippo Precision Co.,Ltd.
20:55 - 21:00 Marubun Corporation

Room: Juyo

Chairperson: K. Tsuruta (DENSO, Japan)

19:00 - 19:05 Evans Analytical Group/Nano Science Corp
19:05 - 19:10 JFE Techno-Research Corporation
19:10 - 19:15 Kobelco Research Institute, Inc.
19:15 - 19:20 Toray Research Center, Inc.
19:20 - 19:25 Nissin Ion Equipment Co.,Ltd.
19:25 - 19:30 Sumitomo Heavy Industries,Ltd.
19:30 - 19:35 centrotherm
19:35 - 19:40 Tokyo Seimitsu co.,LTD.
19:40 - 19:45 Saito Optical Science Manufacturing Ltd.
19:45 - 19:50 Trustwell
19:50 - 19:55 SOL Corporation.
19:55 - 20:00 Rigaku Corporation
20:00 - 20:05 kla-Tencor
20:05 - 20:10 Lasertec Corporation
20:10 - 20:15 Cascade Microtech, Inc.
20:15 - 20:20 SILVACO Japan Co., Ltd.
20:20 - 20:25 Nihon Synopsys G.K.
20:25 - 20:30 Kyocera Corporation
20:30 - 20:35 Ascatron AB
20:35 - 20:40 Raytheon
20:40 - 20:45 Mitsubishi Electric Corporation
20:45 - 20:50 ROHM Co., Ltd.
20:50 - 20:55 Cree Inc.
20:55 - 21:00 YOLE DEVELOPPEMENT